



DATIS: DRAM Architecture and Technology Integrated Simulation

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Background: Why DRAM and DTCO Matter

- DRAM is a cornerstone of modern memory architecture
- DTCO improves DRAM reliability, performance, and efficiency in AI and data-driven systems

2x Intel Sapphire Rapids Server	
Component	AI Server
CPU	\$ 1,850
8 GPU + 4 NVSwitch Baseboard	\$ -
Memory	\$ 3,930
Storage	\$ 1,536
SmartNIC	\$ 654
Chassis (Case, backplanes, cabling)	\$ 395
Motherboard	\$ 350
Cooling (Heatsinks+fans)	\$ 275
Power Supply	\$ 300
Assembly and Test	\$ 495
Markup	\$ 600
Total Cost	\$ 12,800
DRAM BOM %	37.5%
NAND BOM %	14.7%
Memory BOM %	52.2%



DRAM accounts for over 37% of AI server costs

DTCO optimizes:

optimizing system reliability

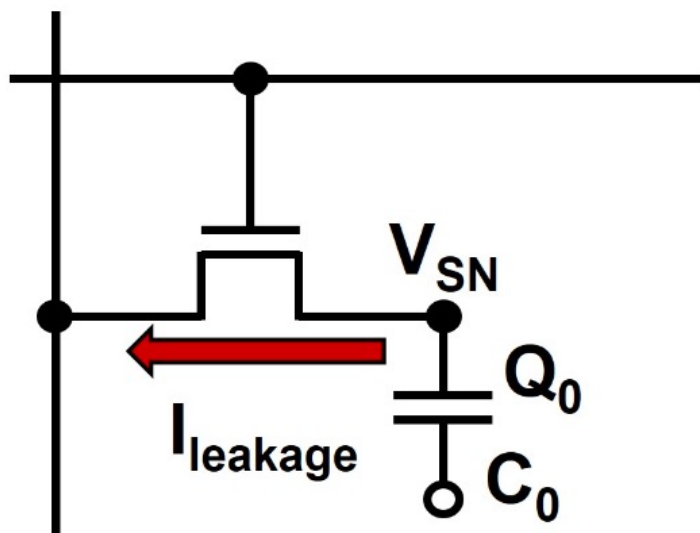
accelerating application kernels

enhancing architectural performance and energy efficiency

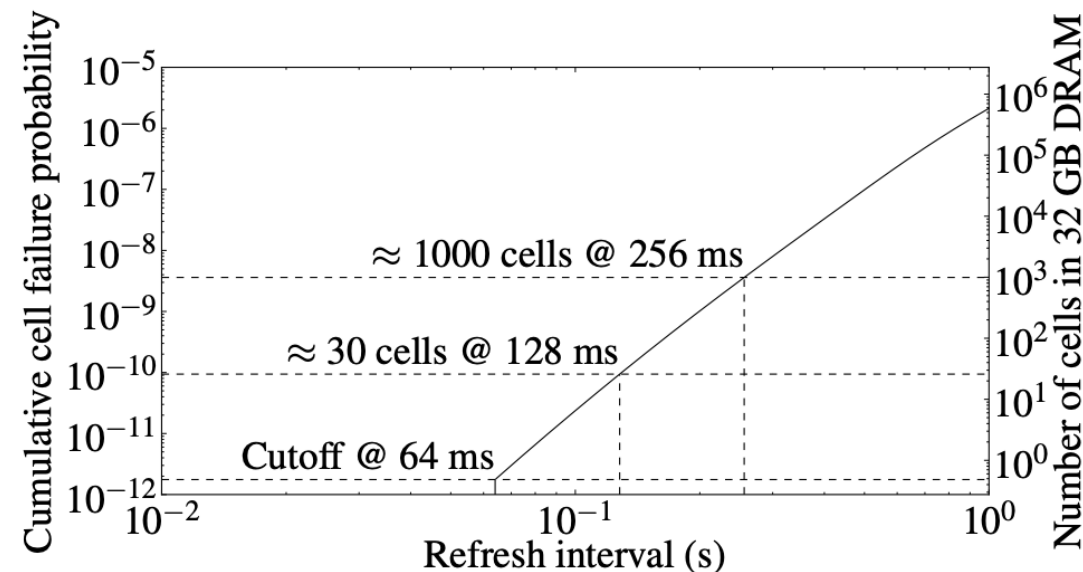
DTCO has become essential

Motivation- DTCO Case I (refresh strategies)

- Retention-aware refresh improves throughput ($\uparrow 50\%$) and power ($\downarrow 40\%$) [1]



DRAM cells leak charge over time

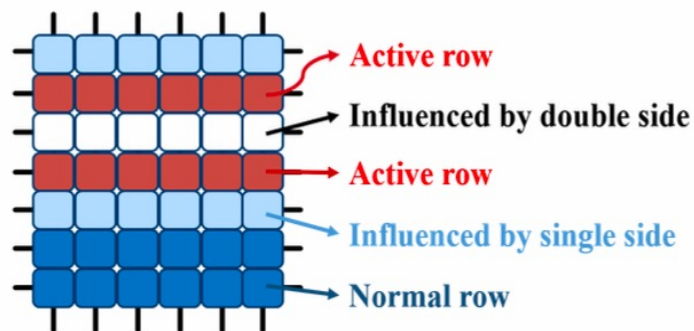


different cells lose charge at different speeds

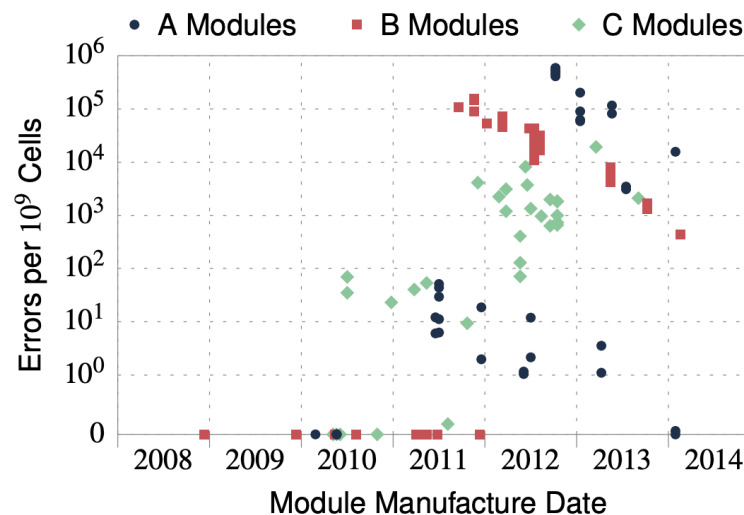
These architecture-level optimizations are highly related to process variation

Motivation- DTCO Case II (RowHammer)

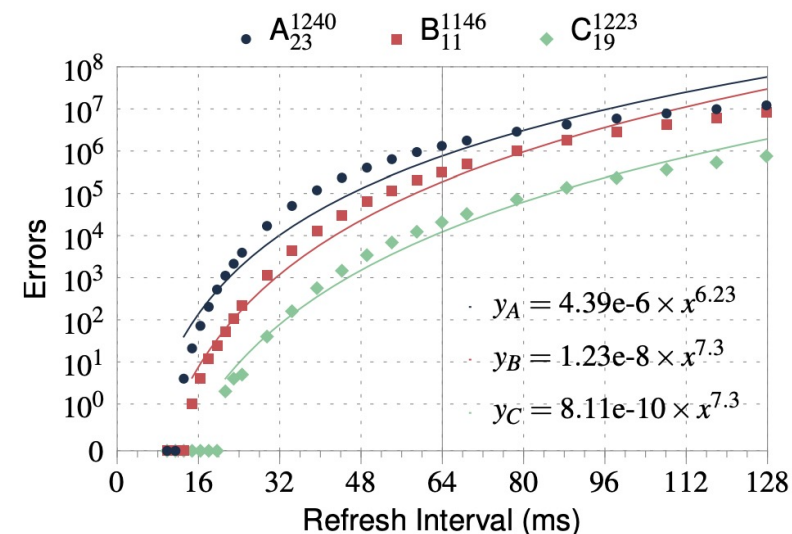
- Mitigate RowHammer effect by new refresh algorithms [1]



RowHammer effect



RowHammer related to process

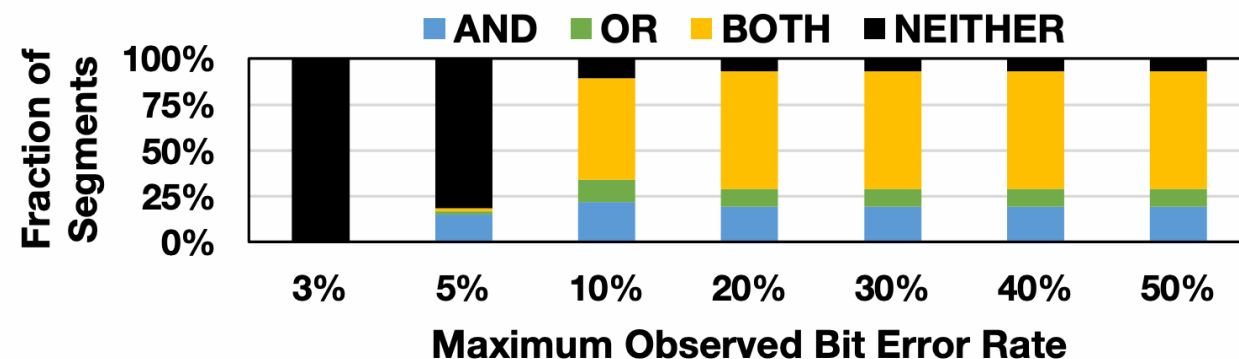
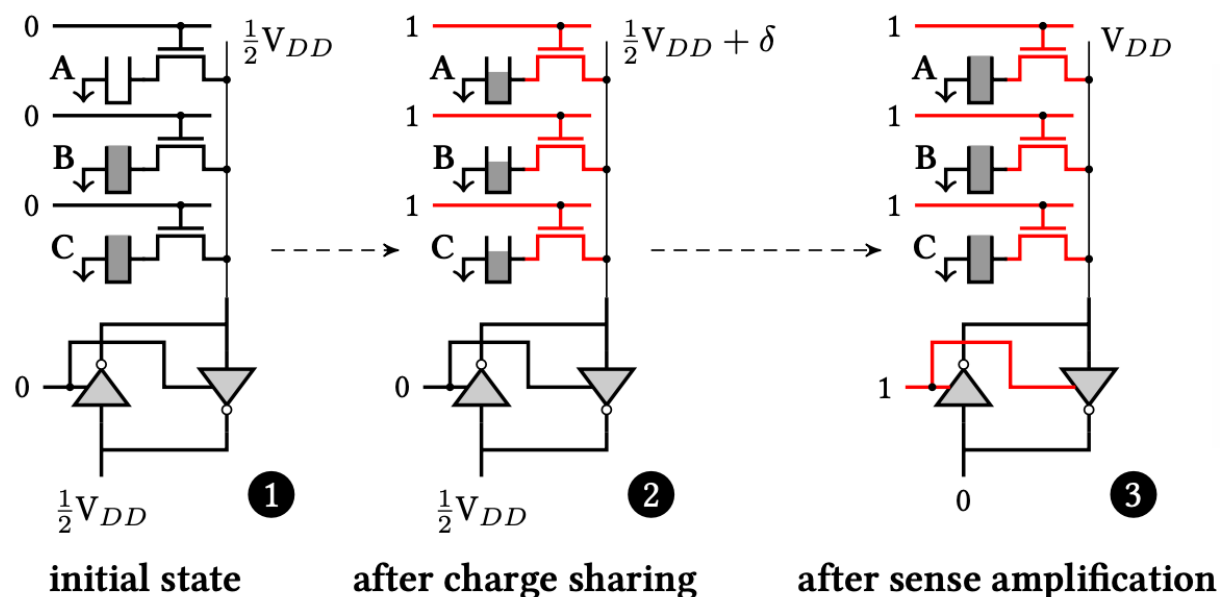


Address RowHammer effect by new refresh algorithm

These optimizations are highly related to process variation

Motivation- DTCO Case III (CIM)

- Error of compute in memory (e.g. bulk bitwise AND and OR operations) related to device-level behavior (e.g. leakage and crosstalk) [1]



[2] Olgun A, Mutlu, O, et al. IEEE TCAD, 2023

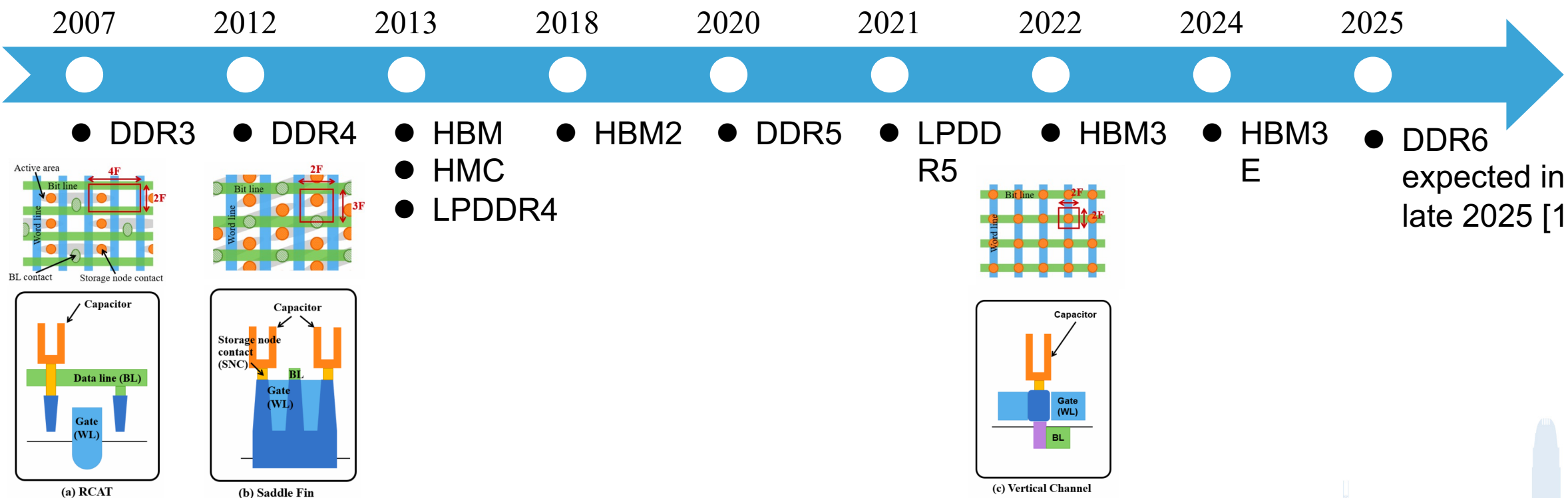
CIM (AND/OR) by charge sharing

Compute error in DRAM due to device-level non-ideal factors (e.g. leakage and crosstalk)

The bit error rate in CIM is highly related to process

Motivation

- DRAM and memory architecture evolve quickly (DDR4, LPDDR5, HBM, HBM3E, DDR6)

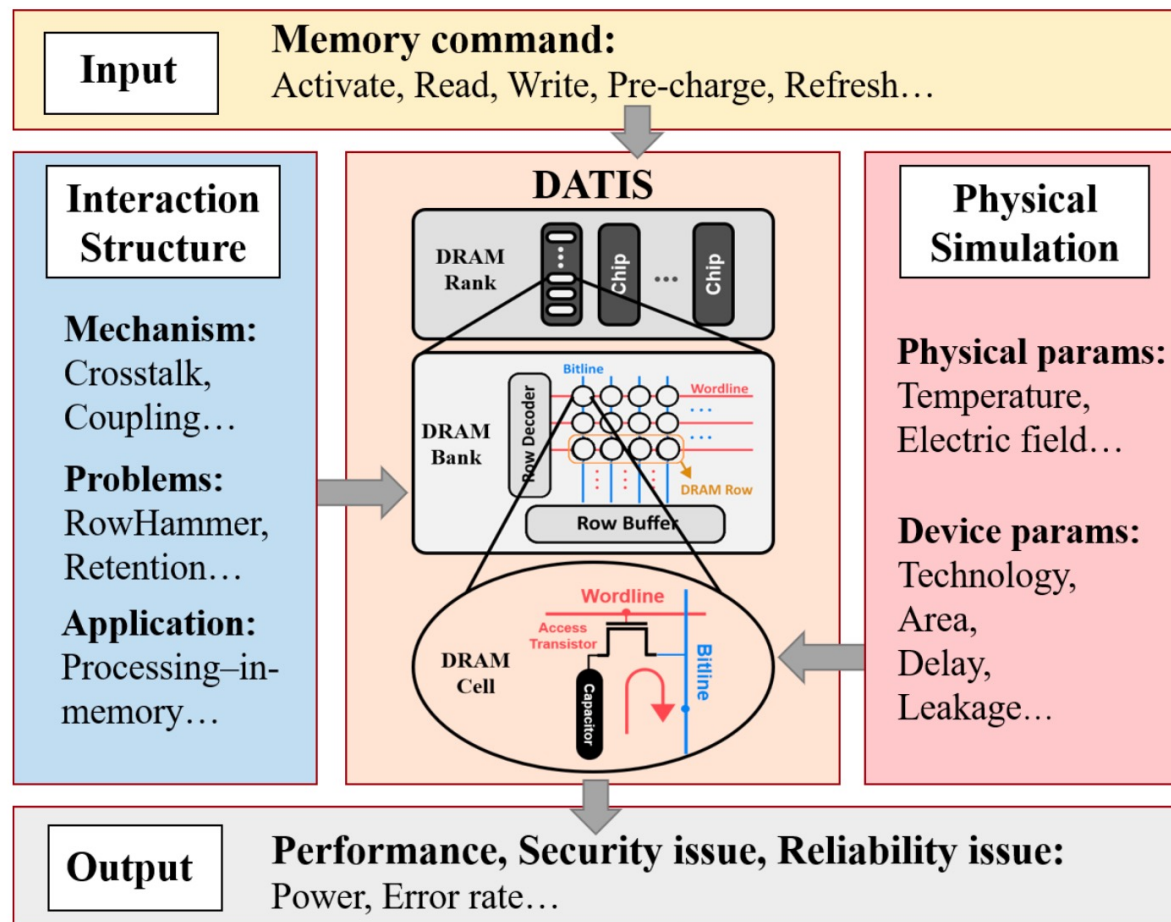


Previous work

- Existing architectural simulators ignore device-level behaviors, which are vital for DTCO studies
- A fast and extensible simulator with device-level models is very much needed

		With device-level model
USIMM	2012	✗
DRAMSim2	2011	✗
DRAMSim3	2020	✗
Ramulator	2015	✗
Ramulator2	2023	✗
This work	2025	✓

What is DATIS

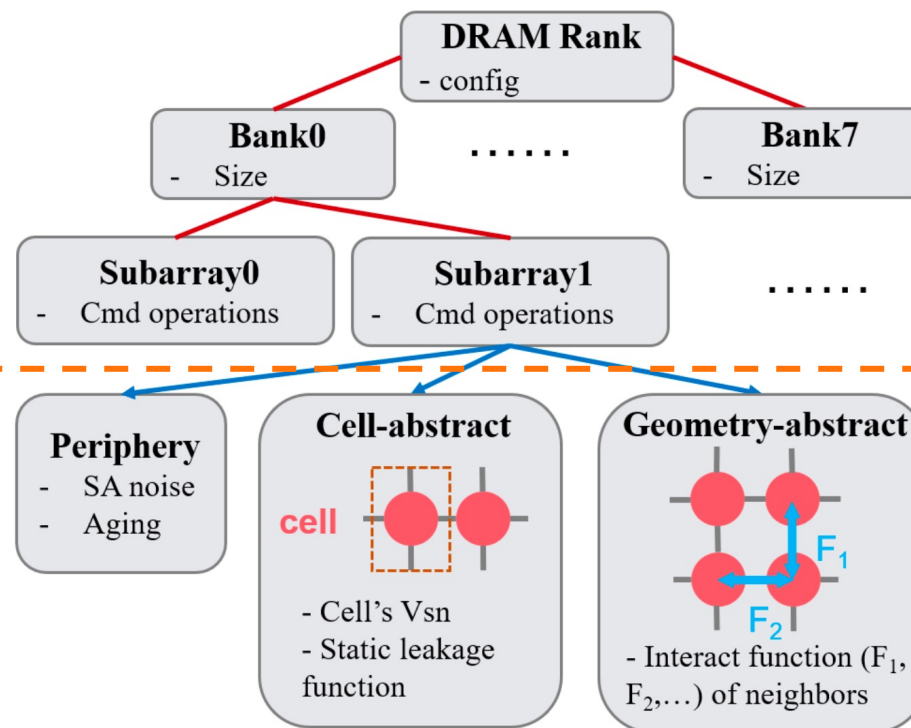


- DATIS bridges DRAM device and architecture
- Based on Ramulator, with analog device modeling
- Supports multiple DRAM standards

Overview of the DATIS Framework

DATIS - Hierarchical structure

- Standard hierarchy (Rank/Bank/Subarray) -- similar to prior work
- Cell/geometry abstraction -- DATIS Highlights



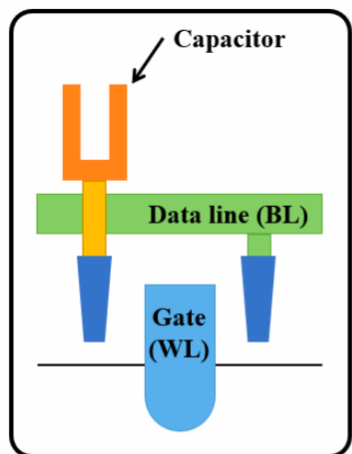
Similar to prior work

DATIS highlight

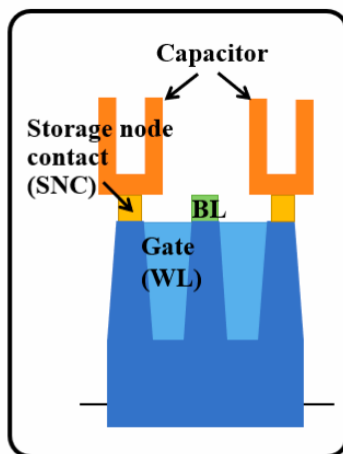
Hierarchical structure of DATIS

DATIS Internals: cell-abstract

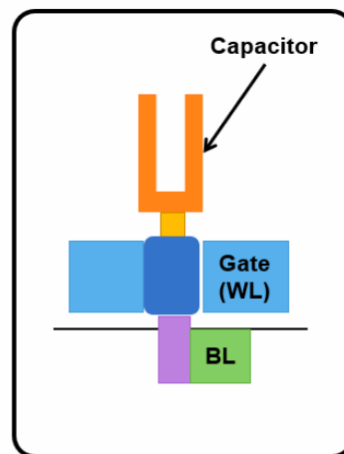
- Supports diverse DRAM cell structures across technologies
- Abstracts them into a unified leakage-aware circuit model



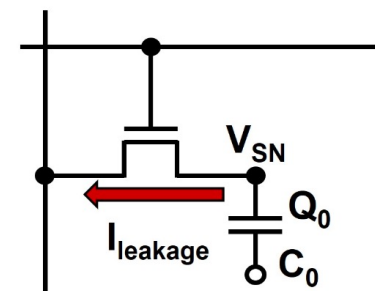
(a) RCAT



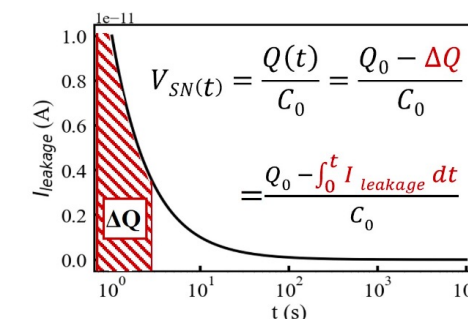
(b) Saddle Fin



(c) Vertical Channel



(a) Leakage Current Diagram



(b) The Leakage Curve Over Time

Mechanism	Types	Formulas
Generation-Recombination	GIDL	$I_{GIDL} = A_{GIDL} \exp\left(-\frac{E_a}{kT}\right)$
	GIJL	$I_{GIJL} = A_{GIJL} \exp\left(-\frac{E_a}{kT}\right)$
Drift-Diffusion	Sub-threshold	$I_{D-D} = A_{D-D} \exp\left(-\frac{E_a}{kT}\right)$
	P-N junction drift/diffusion	
Tunneling through oxide	Gate leakage	$I_{GATE_LEAKAGE} = \sum_{i=1}^n \Delta I_{IT}(i)$
$I_{leakage} = I_{GIDL} + I_{GIJL} + I_{DD} + I_{GATE_LEAKAGE}$		

(c) Table of Leakage Mechanisms and Corresponding Formulas

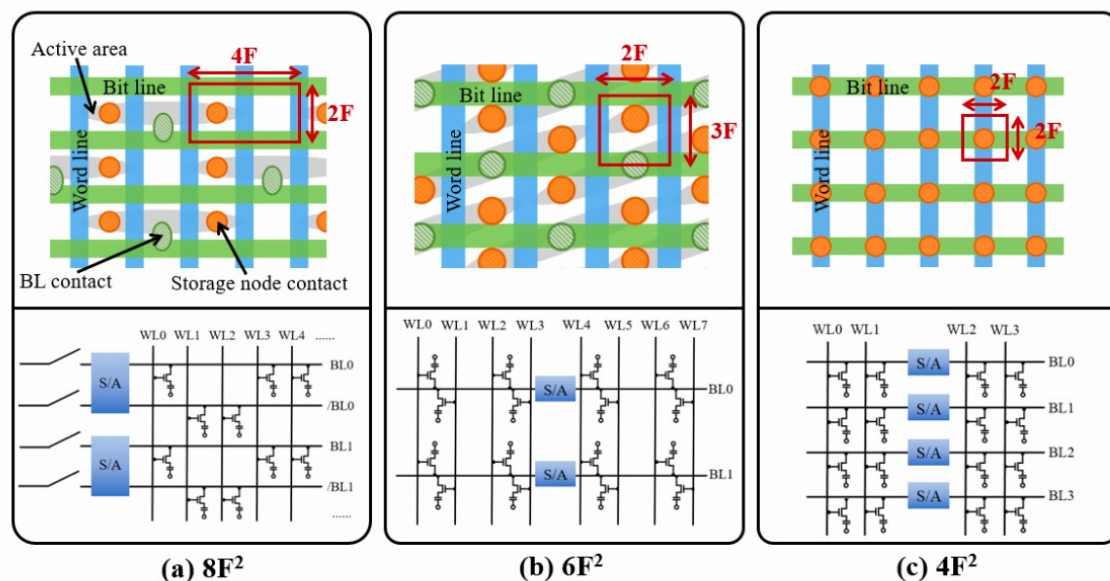
Different DRAM cell structure

Device Leakage Model in DATIS

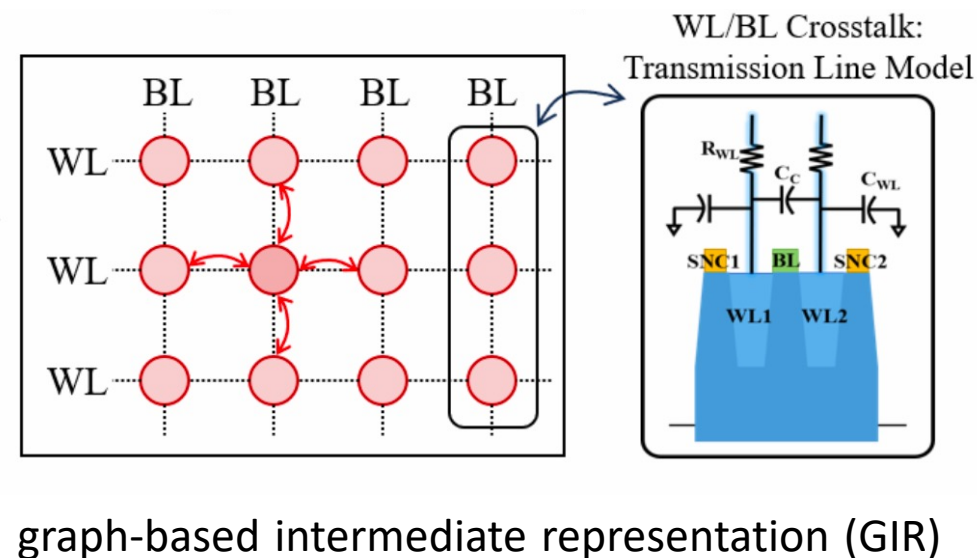
Different DRAM cell designs can be unified under DATIS's cell-abstraction

DATIS Internals: geometry-abstract

- Supports different DRAM process and layout structures
- Abstracts each cell as a node and interactions as edges
- Graph-based modeling enables efficient crosstalk simulation



nodes
edges



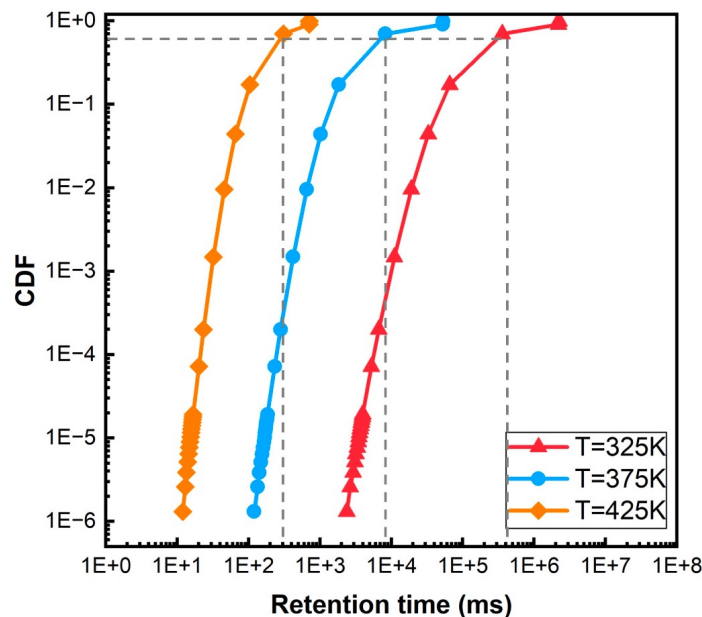
Different DRAM process and geometry structures

Graph IR to model interaction crosstalks.

Crosstalk effects are efficiently modeled under DATIS's geometry-abstract

Case Study I – Retention & Leakage

- DATIS reproduces temperature-dependent retention behavior as observed in prior work

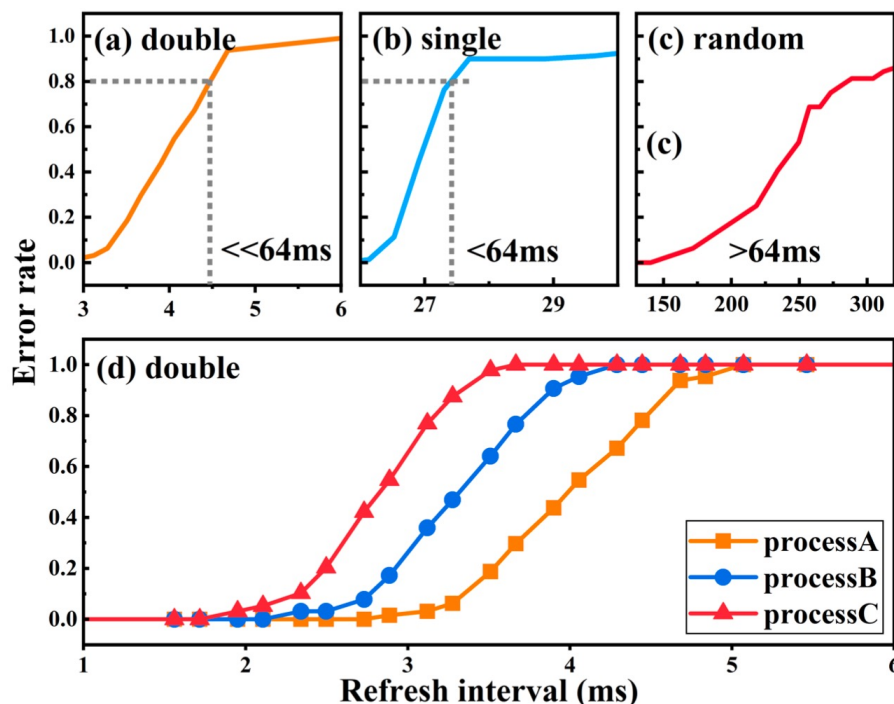


Cumulative distribution function (CDF) of retention time at
325K / 375K / 425K

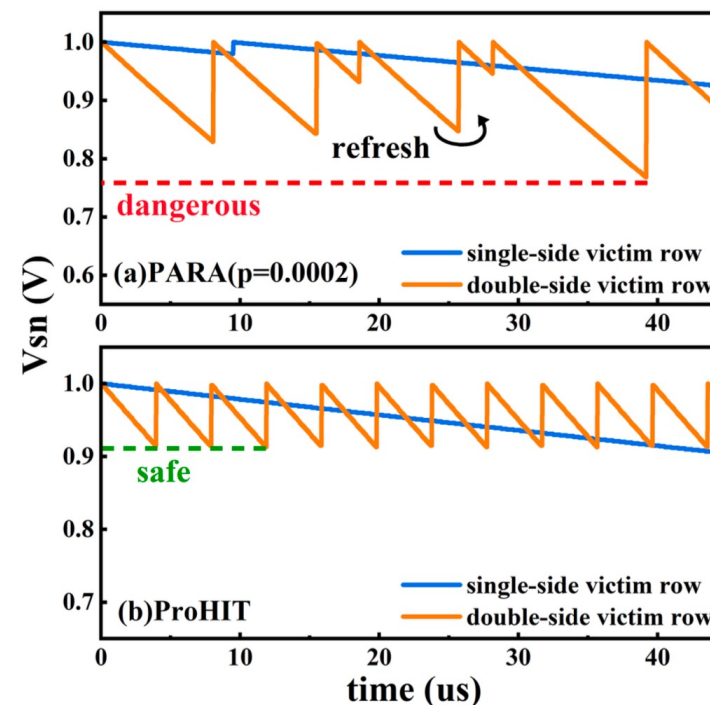
DATIS accurately captures retention times as reported in prior studies

Case Study II – RowHammer

- DATIS reproduces RowHammer error rates and evaluates mitigation algorithms (e.g., PARA, ProHIT)



Error rate with respect to varied access pattern (a-c) and processes (d)

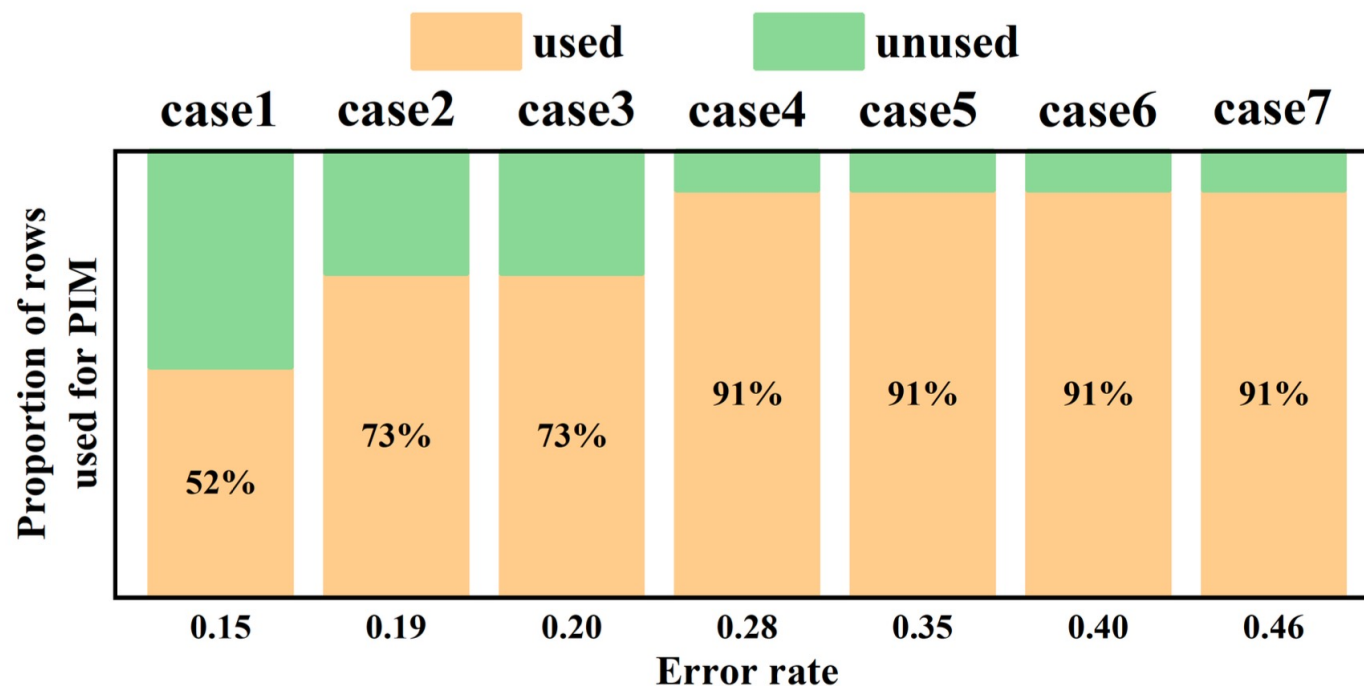


Simulation of two refreshing algorithms for RowHammer

DATIS accurately captures RowHammer effect as reported in prior studies

Case Study III – CIM in DRAM

- DATIS simulates analog CIM behavior and error rates across operation cases



Case	Computation Complexity
Case 1	Convolution x1
Case 2	Convolution x1 & Multiplication x1
Case 3	Convolution x2
Case 4	Convolution x1 & Multiplication x2
Case 5	Convolution x2 & Multiplication x1
Case 6	Convolution x2 & Multiplication x2
Case 7	Convolution x2 & Multiplication x3

Figure 11. Error rate under different cases

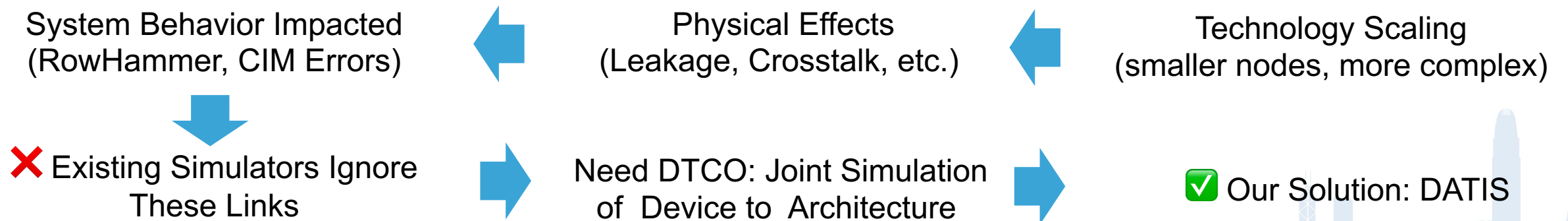
DATIS accurately captures CIM error trends as reported in prior studies

Conclusion

- Extend DATIS to support stochastic computing in DRAM
- Evaluate precision, energy, and variation effects in SC logic
- Enable fast DTCO evaluation of SC-friendly DRAM designs

Future Work

- Extend DATIS to support stochastic computing in DRAM
- Evaluate precision, energy, and variation effects in SC logic
- Enable fast DTCO evaluation of SC-friendly DRAM designs



Q & A

Thank you for your time and attention.
Questions are welcome.

